



FORM PTO-1449  
(Equivalent)

U.S. Department of Commerce  
Patent and Trademark Office

U.S. Application Serial No.  
10/759,857

Atty. Docket No.  
MS-001

INFORMATION DISCLOSURE  
STATEMENT BY APPLICANT

(Use several sheets if necessary)

Boris Kobrin et al.  
Applicants

January 16, 2004  
Filing Date

Unknown  
Group

U. S. PATENT DOCUMENTS

Examiner Initial	Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
<u>AWK</u>	5,576,247	11/19/96	Yano et al.	437	225	
<u>AWK</u>	5,602,671	02/11/97	Hornbeck	359	224	
<u>AWK</u>	5,626,924	05/06/97	Ishikawa	427	759	
<u>AWK</u>	6,203,505	03/20/01	Jalisi et al.	600	585	
<u>AWK</u>	6,383,642	05/07/02	Le Bellac et al.	428	412	
<u>AWK</u>	6,576,489	06/10/03	Leung et al.	438	52	

U. S. PATENT APPLICATION DOCUMENTS

Examiner Initial	Document Number	Publication Date	Name	Class	Subclass	Filing Date
<u>AWK</u>	2001/0028924A1	10/11/01	Sherman	427	255.28	05/24/01
<u>AWK</u>	2002/0031618A1	03/14/02	Sherman	427	569	10/09/01
<u>AWK</u>	2002/0033229A1	03/21/02	Leboutz et al.	156	345	04/20/01

Examiner AWK Date Considered 6/26/05

Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

### U. S. PATENT APPLICATION DOCUMENTS

<u>Examiner Initial</u>	<u>Document Number</u>	<u>Publication Date</u>	<u>Name</u>	<u>Class</u>	<u>Subclass</u>	<u>Filing Date</u>
<u>AW</u>	2002/0076507A1	06/20/02	Chiang et al.	427	569	06/20/02
<u>AW</u>	2002/0146725A1	10/10/02	Mullen et al.	435	6	11/09/01
<u>AW</u>	2002/0195950A1	12/26/02	Mikhael et al.	315	111.21	08/26/02
<u>AW</u>	2003/0035904A1	02/20/03	Hsieh et al.	427	569	08/16/01
<u>AW</u>	2003/0040173A1	02/27/03	Fonash et al.	438	622	08/14/02
<u>AW</u>	2003/0138645A1	07/24/03	Gleason et al.	428	447	10/29/02

### FOREIGN PATENT DOCUMENTS

<u>Examiner Initial</u>	<u>Document Number</u>	<u>Publication Date</u>	<u>Name</u>	<u>Class</u>	<u>Subclass</u>	<u>Filing Date If Appropriate</u>
<u>AW</u>	JP 11116278	04/27/99	Hiromi et al.	C03C	17/28	
<u>AW</u>	WO 02/28956	04/11/02	Murphy et al.	C08L	1/28	

### OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

<u>AW</u>	W. R. Ashurst et al., "Wafer Level Anti-Stiction Coatings With Superior Thermal Stability", Presentation at Hilton Head, South Caroline meeting, pp 1 - 4 (June 2002). Contact ashurbr@uclink4.berkeley.edu.
<u>AW</u>	W. R. Ashurst et al., "Vapor Phase Anti-Stiction Monolayer Coatings for MEMS", TDMR-Draft, pp. 1 - 6 (Sept 2003).
<u>AW</u>	W. R. Ashurst et al., "Wafer level anti-stiction coatings for MEMS", Sensors and Actuators A, Elsevier Science B.V., Vol. 104, pp. 213 - 221 (2003).

<u>Examiner</u> <u>Initial</u>	<u>Date Considered</u>
<u>AW</u>	<u>6/26/05</u>

Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

---

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

---

- AK M. V. Collins et al., "Optimization of Anodic Bonding to MEMS with Self-Assembled Monolayer (SAM) Coatings", Reliability, Testing, and Characterization of MEMS/MOEMS, Proceedings of SPIE, Vol. 4558, pp. 234 - 241 (2001).
- AK M. G. Hankins, "Vapor Deposition of Amino-Functionalized Self-Assembled Monolayers on MEMS", Reliability, Testing, and Characterization of MEMS/MOEMS, Proceedings of SPIE, Vol. 4980, pp. 238 - 247 (2003).
- AK S. A. Henck, "Lubrication of digital micromirror devices™", Tribology Letters, Vol. 3, pp. 239 - 247 (1997).
- AK P. W. Hoffmann et al., "Vapor Phase Self-Assembly of Fluorinated Monolayers on Silicon and Germanium Oxide", Langmuir, Vol. 13, pp. 1877 - 1880 (1997).
- AK A. Hozumi et al., "Amino-terminated self-assembled monolayer on a SiO<sub>2</sub> surface formed by chemical vapor deposition", J. Vac. Sci. Technol. A, Vol. 19, No. 4, pp. 1812 - 1816 (Jul/Aug 2001).
- AK X. Jia et al., "Controlled Growth of Silicon Dioxide from 'Nanoholes' in Silicon-Supported Tris(trimethylsiloxy)silyl Monolayers: Rational Control of Surface Roughness at the Nanometer Length Scale", Langmuir, Vol. 19, pp. 2449 - 2457 (2003).
- AK B. H. Kim, "A New Organic Modifier for Anti-Stiction", Journal of Microelectromechanical Systems, Vol. 10, No. 1, pp. 33 - 40 (March 2001).
- AK T. M. Mayer et al., "Chemical vapor deposition of fluoroalkylsilane monolayer films for adhesion control in microelectromechanical systems", J. Vac. Sci. Technol. B, Vol. 18, No. 5, pp. 2433 - 2440 (Sep/Oct 2000).
- AK J. Sakata et al., "Anti-Stiction Silanization Coating to Silicon Micro-Structures by a Vapor Phase Deposition Process", Transducers, pp. 1 - 4 (1999).
- AK J. Wang et al., "Gold nanoparticulate film bound to silicon surface with self-assembled monolayers", Thin Solid Films, Elsevier Science S.A., pp. 591 - 594 (1998).
- AK X. Wang et al., "Gas-Phase Silicon Etching with Bromine Trifluoride", Transducers, International Conference on Solid State Sensors and Actuators, Chicago, pp. 1505 - 1508 (June 1997).
- AK Y. Wang et al., "Vapor phase deposition of uniform and ultrathin silanes", SPIE, Vol. 3258, pp. 20 - 28 (1998).

---

Examiner

Date Considered

AK

6/26/05

---

Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

---